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OCT 10 2002

TC 1700

ABSTRACT OF THE DISCLOSURE

*Please replace the text of the abstract of the disclosure  
currently on file with the following text:*

A semiconductor manufacturing apparatus, composed in part of a vacuum vessel, is capable of uniform processing of a substrate while occupying a small floor area and being readily maintainable. The apparatus includes at least one substrate stage provided on a vacuum vessel bottom plate and a cylinder surrounding the substrate stage. At least one cylinder lifting/lowering mechanism per cylinder is provided, in order to separate a space inside the cylinder, composing a processing chamber for processing the substrate surface, from a space outside the cylinder, composing a transport chamber for transferring the substrate. The transport chamber is provided with a substrate conveyer mechanism.